

## IN THE SPECIFICATION

At page 2, lines 9-19, of the substitute specification, please delete the three paragraphs therein and substitute in their place the following three amended paragraphs:

B1  
-- Figure 1 shows an overall diagrammatic view of an inspection device consisting of a laser module LM with a pulsed UV laser, a coupling unit UP, a microscope MI with an objective O and a scanning table ST, a CCD camera KA, a screen BS and a microscope controller MC with scanning tables controls for driving X, Y, and Z directions and an MSM 193 control. A MCU 27 Control Panel 27 is connected to Microscope Controller MC. Also shown is the System Control PC computer with communication ports COM1, COM2, COM3, COM4 shown as well as LPT port Also shown is a PCI bus from the camera controller. A VIS lamp is also shown.

Figure 2a and 2b show a coupling unit UP for coupling the laser beam into the microscope MI.

The laser light reaches a first rotating diffusion disk S1 via reflecting mirrors U1, U2 and then a second rotating diffusion disk S2 preferably rotating in the opposite direction as well as the microscope ray path (not shown) via a lens L for beam expansion and an aperture B and the input E in Figure 1 and illuminates the object to be examined.--

At page 3, lines 5-6 of the substitute specification please replace the paragraph found therein with the amended paragraph below:

B2  
-- The homogenizing effect is reinforced by a second diffusion disk rotating in the opposite direction. The microscope may include two diffusion disks rotating in opposite directions arranged directly or indirectly behind each other in the illumination ray path. The microscope may include the structure that the diffusion disk is either of a granulated or of a holographically produced design. The microscope may use a rotation speed of at least such a magnitude that a rotation by at least one grain size and/or the resolution limit of a holographically generated structure or by the length of a structure takes place between two laser pulses. The microscope may use an illumination laser wavelength which essentially corresponds to the illumination wavelength during the manufacture of semiconductors. The microscope may use an illumination

Cont'd  
B2 wavelength is in the range of 193nm or 248nm or 266nm or 366nm, all with a tolerance of +/-  
2nm. --

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